

ABSTRACT OF THE DISCLOSURE

A resist is stacked on a substrate with a lower layer film in between. The lower layer film is composed in such a way that the element absorbing the largest amount of x-rays of all the elements contained here is the
5 element C. The film thickness of the lower layer film is determined by considering the influence of secondary electrons from the substrate and that of the element C of the lower layer film. The resist has added thereto an element Cl or a similar element having a specific absorption edge. Under such conditions, x-rays are irradiated such that the average wavelength
10 absorbed in the resist is in a prescribed range. In this way, x-ray exposure can be performed while blur caused by secondary electrons is suppressed using a wavelength region of relatively shorter wavelengths.